

IN THE CLAIMS:

Please amend claim 22 as follows:

22. (Twice Amended) A method for fabricating a device
using an exposure apparatus comprising the steps of:

emitting a luminous flux from a light source;

projecting the luminous flux through an illumination
system;

disposing a reticle having a pattern formed thereon
along a path traveled by the luminous flux;

providing a titanium oxide film on at least a portion
of a surface of a unit of the exposure apparatus;

[aligning the reticle with a wafer by an exposure
apparatus that includes at least one unit having a surface on at
least a portion of which a titanium oxide film is provided;]

exposing a [the] wafer with the [a] pattern formed on
the reticle by illuminating the pattern with the luminous flux
emitted from the light source and projected through the
illumination system[, said exposing step being performed after
said aligning step]; and

developing the wafer.